

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kazuo USHIDA et al.

Application No.: 09/320,472

Filed: May 25, 1999

For: PROJECTION EXPOSURE APPARATUS

Group Art Unit: 2851

Examiner: A. Mathews

Docket No.: 110197.98

#1316
11-13-01
agaSUPPLEMENTAL AMENDMENT IN REISSUE APPLICATIONDirector of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Further to the Amendment filed September 4, 2001, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claims 120 and 121 without prejudice to or disclaimer of the subject matter contained therein.

Please replace claims 28, 97, 104, 105, 113, 122-124, 127 and 128 with the following amended claims:

39 ~~28~~ (Three Times Amended) A projection exposure apparatus comprising:
an illumination optical system disposed in an optical path of light emitted by a
light source so as to illuminate a mask. the illumination optical system including an optical
system disposed in an optical path between the light source and the mask so as to form an
annular illumination source, said optical system changing an annular ratio of the annular
illumination source in accordance with a pattern formed on the mask; and
a projection optical system disposed in an optical path between the mask and a
substrate so as to project an image of the mask onto the substrate, said projection optical